## Oxford Instruments Plasma Technology & The Kavli Nanoscience Institute present

workshop

Etch Tech 2012: Pushing the Limits

July 16-17, 2012 California Institute of Technology, Pasadena, CA, USA

This workshop is open to all those people working in industry and academia, with an interest in recent progress in research and development, plus future trends in the fabrication and application of micro & nano structures and devices.



## Monday, July 16

Hameetman Auditorium, Cahill Center for Astronomy and Astrophysics

Speaker	Topic
Dan Ayres, Managing Director, Oxford Instruments	Introduction to Oxford Instruments
Michelle Bourke, Oxford Instruments	Advances in Deep RIE / MEMS
Dr. Andrei Faraon, Caltech	Diamond Etching
Bob Gunn, Oxford Instruments	III V Etch for Nano Device Applications
Dr Michael Hochberg, University of Delaware	OpSIS Optoelectronics Systems Integration in Silicon
Dr Rassul Karabalin, Caltech	Fabrication of Piezoelectric Nanoelectromechanical Systems
Dr Zuwei Liu, LBNL/ Oxford Instruments	Nanoscale Applications of ALD
Dr Deirdre Olynick, Molecular Foundry, LBNL	Single Digit Nanoscale Fabrication
Dr Oskar Painter, Co-Director of the KNI, Caltech	Silicon Etching for Nanomechanics
Dr Sameer Walavalkar, Caltech	Three Dimensional Etching of Silicon Nanostructures

## Tuesday, July 17

KNI Conference Room, room 125, Steele Laboratory

Speaker/Facilitator	Tutorial Topic
Leslie Lea, Principal Technologist, Oxford Instruments	Diagnostics and Etching
Craig Ward, Oxford Instruments	Process Recovery and cross Contamination prevention
Annika Peter Oxford Instruments	ALD Tutorial

To register for this event, or for further information, please visit our event website.

## Space is Limited!

There is no charge for this two-day workshop, but all participants need to register.



